

After the title, please include the following

RELATED APPLICATION

A 1 This application is a continuation of pending United States Application Serial Number 08/795,379 filed February 4, 1997.

On page 6, at the end of the section entitled DESCRIPTION OF THE FIGURES, please add

A 2 Figure 3 is a schematic drawing of another process chamber suitable for use with an exemplary embodiment of the current invention.

A 3 On page 9, line 4, please replace "tertakis (diethylamino)" with -- tetrakis (dimethylamino) --.

A 4 On page 11, line 23, after the sentence ending in "chambers." please add
In addition to the chamber depicted in figure 1, embodiments within the scope of the current invention apply to other types of processing chambers as well, including the one depicted in Figure 3. In that figure, system 100 includes a plasma generator 108 and a furnace tube 102. The furnace tube 102 comprises a ceramic shell 104 around a quartz tube 106 and is configured to hold substrate 20. Coupling the furnace tube 102 to a remote plasma chamber 40 allows for cleaning methods as described above.

A 5 On page 20, in the Abstract, please complete the sentence ending on line 9 with
chamber; and any conductive material is in-situ removed from the inside of the chamber to remove any blocking of the inductive power couple to the reaction chamber.

IN THE CLAIMS

Please cancel claims 1-40.

Please add the following claims.